

Solutions

HW #5

ECE 606

(2)

sol
Problem 4A:

The continuity equation for the excess hole is given by:

$$\frac{\partial \Delta p}{\partial t} = \frac{1}{q} \frac{\partial J_p}{\partial x} - r_p + g_p$$

For steady state, dark room and low level recombination, we have

$$\frac{1}{q} \frac{\partial J_p}{\partial x} - \frac{\Delta p}{\tau_p} = 0$$

The steady state current is given by:

$$J_p = q \mu E \Delta p - q D_p \frac{\partial \Delta p}{\partial x}$$

Substitute back into continuity equation we get,

$$D_p \frac{\partial^2 \Delta p}{\partial x^2} - \mu E \frac{\partial \Delta p}{\partial x} - \frac{\Delta p}{\tau_p} = 0$$

Using the hint, we have the following roots,

$$r = \frac{\mu E \pm \sqrt{(\mu E)^2 + \frac{4D_p}{\tau_p}}}{2D_p}$$

Hence

$$\mu E + \sqrt{(\mu E)^2 + \frac{4D_p}{\tau_p}} \quad \text{and} \quad r_2 = \frac{\mu E - \sqrt{(\mu E)^2 + \frac{4D_p}{\tau_p}}}{2D_p}$$

$$\Delta p(x) = c_1 \exp(r_1 x) + c_2 \exp(r_2 x)$$

To determine c_1 and c_2 we make use of boundary condition.

$$\Delta p(0) = c_1 + c_2$$

$$\Delta p(L) = c_1 \exp(r_1 L) + c_2 \exp(r_2 L) = 0$$

$$\Rightarrow c_1 = -c_2 \exp((r_2 - r_1)L)$$

Therefore the final solution is:

$$\Delta p(x) = \frac{\Delta p(0)}{1 - \exp((r_1 - r_2)L)} \exp(r_1 x) + \frac{\Delta p(0)}{1 - \exp((r_2 - r_1)L)} \exp(r_2 x)$$

Problem 4B:

$$D_p = \frac{kT}{q} \mu_p = 10 \text{ cm}^2 / \text{s}$$

We have also the following constants for

$$\Delta p(x) = c_1 \exp(r_1 x) + c_2 \exp(r_2 x)$$

$$r_1 = 1.22 \times 10^5$$

$$r_1 = -8.2 \times 10^4$$

$$c_1 = -1.5 \times 10^{20}$$

$$c_2 = 1.15 \times 10^{21}$$

The drift current at $x=0$ is given by:

$$q\mu E \Delta p = 6.41 \times 10^3 \text{ A/m}^2$$

The diffusion current at $x=0$ is given by;

$$-qD_p \frac{\partial \Delta p}{\partial x} = 1.8 \times 10^4 \text{ A/m}^2$$

Supposed now we assume $E=0$,

$$r_1 = 1.0 \times 10^5$$

$$r_1 = -1.0 \times 10^5$$

$$c_1 = -1.57 \times 10^{20}$$

$$c_2 = 1.157 \times 10^{21}$$

$$-qD_p \frac{\partial \Delta p}{\partial x} = 2.1 \times 10^4 \text{ A/m}^2$$

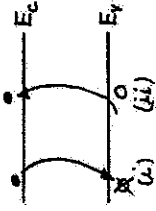
The fraction error introduced is approximately 0.167.

Problem 4C:

False, True, False, False

Discard

(5.10)
(a)



(b) RECOMBINATION... We note first of all that $\frac{\partial M}{\partial t}|_R = \frac{\partial P}{\partial t}|_R$. Also, following a text-like argument, the recombination rate is expected to be proportional to both n and p , the electron and hole concentrations. Letting c_b be the proportionality constant, we conclude

$$\frac{\partial M}{\partial t}|_R = \frac{\partial P}{\partial t}|_R = -c_b n p \quad (c_b \geq 0)$$

GENERATION... The generation rate, $\frac{\partial M}{\partial t}|_G = \frac{\partial P}{\partial t}|_G$, should depend on the number of filled states in the valence band and on the number of empty states in the conduction band. If the semiconductor is taken to be nondegenerate, both of the cited quantities are approximately constant. Thus

$$\frac{\partial M}{\partial t}|_G = \frac{\partial P}{\partial t}|_G = \beta = \text{constant}$$

Combining the above relationships yields

$$r_b = -\left(\frac{\partial M}{\partial t}|_R + \frac{\partial M}{\partial t}|_G\right) = -\left(\frac{\partial P}{\partial t}|_R + \frac{\partial P}{\partial t}|_G\right) = c_b n p - \beta$$

Next invoking the equilibrium simplification based on the principle of detailed balance gives

$$r_b|_{\text{EQUILIBRIUM}} = 0 = c_b n_0 p_0 - \beta_0$$

$$\text{or } \beta_0 = c_b n_0 p_0 = c_b n_i^2$$

Making the usual assumption that β and c_b do not change significantly under non-equilibrium conditions then yields

and $\beta = \beta_0 = C_b m_i^2 = C_b m_i^2$

$[r_b = C_b (m_p - m_i^2)]$

(c) Letting $M = m_0 + \Delta M$
 $P = p_0 + \Delta P = p_0 + \Delta M$
 and substituting into the r_b expression gives
 $r_b = C_b (m_0 p_0 + m_0 \Delta M + p_0 \Delta M + \Delta M^2 - m_i^2)$
 $= C_b (m_0 + p_0) \Delta M$
 ← neglect for low level injection

or

$r_b = \frac{\Delta M}{\tau_b}$
 $\tau_b = \frac{1}{C_b (m_0 + p_0)}$

(d) A nondegenerate doping in silicon at 300K corresponds to a doping of N_D or $N_A \leq 10^{18}/cm^3$. Thus the typical range of interest for $m_0 + p_0$ is $10^{14}/cm^3 \leq m_0 + p_0 \leq 10^{18}/cm^3$. Computing τ_b from the part (c) result with $C_b = 5 \times 10^{15} cm^3/sec$, and comparing against the worst case scenario ($\tau_{R6, carrier} = 1$ msec for p-type Si) as deduced from Fig 5.11, we obtain

N_D or $N_A (cm^{-3})$	$\tau_b (sec)$	$\tau (\text{Fig 5.11}) (sec)$
10^{14}	2×10^{-1}	1×10^{-3}
10^{16}	2×10^{-2}	1×10^{-3}
10^{17}	2×10^{-3}	6×10^{-4}
10^{18}	2×10^{-4}	1×10^{-5}

For this worst case scenario, τ_b is $\geq 20 \times \tau$ over most of the doping range, only dropping to $\sim 3 \times \tau$ near $N_D = 10^{17}/cm^3$. Clearly one seldom has to worry about band-to-band recombination in nondegenerately doped Si at room temperature.

Q2 Intrinsic silicon at 300 K.

$$n_0 = p_0 = n_i = 10^{10} \text{ cm}^{-3}$$

$$\mu_n = 1360 \text{ cm}^2/\text{V}\cdot\text{s}$$

$$\mu_p = 460 \text{ cm}^2/\text{V}\cdot\text{s}$$

$$f = \frac{1}{q(\mu_n n + \mu_p p)} = \frac{1}{1.6 \times 10^{-19} (1360 + 460) \times 10^{10}} = 3.93 \times 10^5 \text{ } \Omega/\text{cm}$$

n-doped silicon $N_D = 10^{16} \text{ cm}^{-3}$ (300 K)

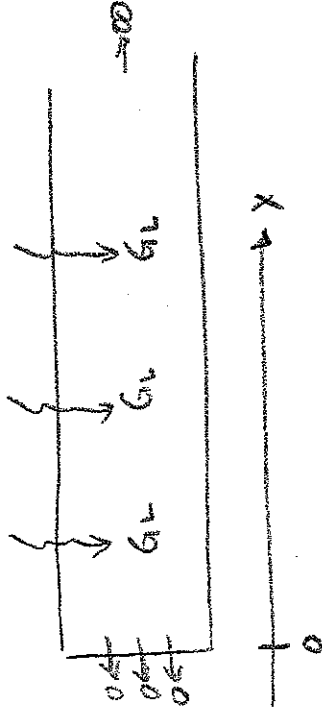
$$f = \frac{1}{q \mu_n N_D} = \frac{1}{1.6 \times 10^{-19} \times 1360 \times 10^{16}} = 0.46 \text{ } \Omega/\text{cm}$$

⑤

Q4

4. A semi-infinite n-type semiconductor bar is subject to uniform penetrating illumination resulting in a generation rate of G_L electron-hole pairs per second per cm^2 throughout the bar. G_L is such that sample remains in low-level injection. Minority carriers are extracted at the surface at $x = 0$. Obtain an expression for the maximum hole current that can be drawn from the bar in steady-state.

[20 pts]



MCDE:
$$\frac{\partial \Delta p_n}{\partial t} = 0 = D_p \frac{\partial^2 \Delta p_n}{\partial x^2} - \frac{\Delta p_n}{\tau_p} + G_L$$

GEN'L SOLN:
$$\Delta p_n(x) = A e^{-x/L_p} + B e^{x/L_p} + \tau_p G_L$$

BC: at $x = \infty$, Δp_n must be finite, so set $B = 0$.
 at $x = 0$, to extract holes at the highest possible rate, set $p_n(0) = 0$. Then

$$\Delta p_n(0) = p_n(0) - p_{n0} = -p_{n0}$$

$$\therefore \Delta p_n(0) = A e^0 + \tau_p G_L = -p_{n0}$$

so
$$A = -(p_{n0} + \tau_p G_L)$$

and
$$\Delta p_n(x) = \tau_p G_L - (p_{n0} + \tau_p G_L) e^{-x/L_p}$$

$$J_p(x) = -q D_p \frac{\partial \Delta p_n}{\partial x} = -q \frac{D_p}{L_p} (p_{n0} + \tau_p G_L) e^{-x/L_p}$$

and
$$J_p(0) = -q \frac{D_p}{L_p} (p_{n0} + \tau_p G_L)$$

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16/00

3. Consider a region in a semiconductor that is totally depleted of carriers ($n = p = 0$). Obtain an expression for the energy level of the RG centers relative to midgap $\Delta E = (E_T - E_i)$ that results in the highest possible generation rate. Your answer should include the minority carrier lifetimes τ_n and τ_p .

[20 pts]

$$R = \frac{pn - n_i^2}{\tau_n(p+p_i) + \tau_p(n+n_i)} \quad \begin{cases} n_i = n_i e^{(E_T - E_i)/kT} \\ p_i = n_i e^{(E_i - E_T)/kT} \end{cases}$$

If $n=p=0$, $-R=G = \frac{n_i^2}{\tau_n p_i + \tau_p n_i}$

$$G = \frac{n_i^2}{\tau_n n_i e^{(E_i - E_T)/kT} + \tau_p n_i e^{(E_T - E_i)/kT}}$$

Let $(E_T - E_i) = \Delta E$, then $G = \frac{n_i^2}{\tau_n e^{-\Delta E/kT} + \tau_p e^{\Delta E/kT}}$

Set $\frac{dG}{d\Delta E} = 0$ to find the maximum generation rate.

$$\frac{dG}{d\Delta E} = \frac{(-n_i^2)}{(\tau_n e^{-\Delta E/kT} + \tau_p e^{\Delta E/kT})^2} \left(-\frac{\tau_n}{kT} e^{-\Delta E/kT} + \frac{\tau_p}{kT} e^{\Delta E/kT} \right) = 0$$

$$\therefore \tau_p e^{\Delta E/kT} - \tau_n e^{-\Delta E/kT} = 0$$

Multiply by $e^{\Delta E/kT}$ gives $\tau_p e^{2\Delta E/kT} = \tau_n$

$$e^{2\Delta E/kT} = \frac{\tau_n}{\tau_p} \rightarrow \Delta E = E_T - E_i = \frac{kT}{2} \ln\left(\frac{\tau_n}{\tau_p}\right)$$

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